

Instructions: This is a 50-minute exam. Students may bring 2 pages of notes (front and back) to this exam. There are 10 short question is worth 2 points each and 5 problems worth 16 points each. Please solve problems in the space provided on this exam and attach extra sheets only if you run out of space in solving a specific problem.

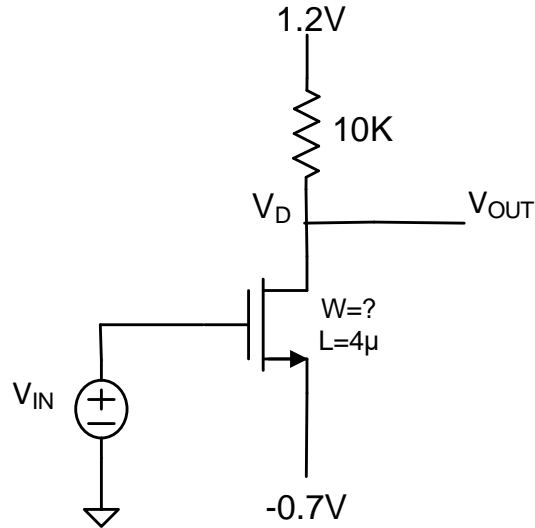
If references to semiconductor processes are needed beyond what is given in a specific problem or question, assume all n-channel MOS transistors have model parameters $\mu_n C_{OX} = 350 \mu A/V^2$ and $V_{Tn} = 0.5V$, all p-channel transistors have model parameters $\mu_p C_{OX} = 70 \mu A/V^2$ and $V_{Tp} = -0.5V$. Correspondingly, assume all npn BJT transistors have model parameters $J_S = 10^{-14} A/\mu^2$ and $\beta = 100$ and all pnp BJT transistors have model parameters $J_S = 10^{-14} A/\mu^2$ and $\beta = 25$. If the emitter area of a transistor is not given, assume it is $100 \mu^2$. If parameters are needed for CMOS process characterization beyond what is given, use the measured parameters from the TSMC 0.18 μ process given below as model parameters. Assume all diodes are characterized by the model parameters $J_{SX} = 0.5 A/\mu m^2$, $V_{G0} = 1.17V$, and $m = 2.3$.

1. (2 pts) What is the purpose of the n+ buried collector in a bipolar process?
2. (2 pts) What region of operation in a bipolar transistor corresponds to the triode region of operation in a MOS transistor?
3. (2pts) What parameter in a JFET corresponds to the threshold voltage in a MOSFET?
4. (2 pts) In a CMOS process that has a single polysilicon layer, it can be observed that after processing, polysilicon appears either on top of thin oxide or on top of thick oxide. What must the designer do to place polysilicon on top of thin oxide?
- 5 (2 pts) How many small-signal parameters are required to characterize an arbitrary 4 terminal nonlinear device?
6. (2pts) When biasing either MOS or Bipolar transistors, the Q-point is often placed near the middle of the load line. What is the major reason this is often done?

7. (2pts) If a large current dc current is inserted into the control gate of an SCR, the I-V characteristics of the SCR are similar to another device we have studied. What is that device?
8. (2pts) When analyzing nonlinear circuits with a small-signal excitations, the nonlinear device models can always be used but often small-signal models are used instead. What is the major reason small-signal models are often used to analyze nonlinear circuits with small-signal excitations?
9. (2pts) When doing a small-signal analysis, the Q-point must almost always be determined as well. What is the major reason the Q-point is needed for a small-signal analysis of a circuit with nonlinear devices?
10. (2pts) In a standard bipolar process, MOS transistors are not available. Yet, there is a device that is available in a bipolar process that is also a square-law device with nearly 0 input current. What device is this?

Problem 1 (16 pt) Consider the following circuit.

- Draw the small signal equivalent circuit assuming the MOS transistor is operating in the saturation region
- Give the small-signal voltage gain in terms of the small-signal model parameters assuming the MOS transistor is operating in the saturation region
- Determine W so that the quiescent output voltage is $0V$
- Determine the small-signal voltage gain with the value of W determined in part c)



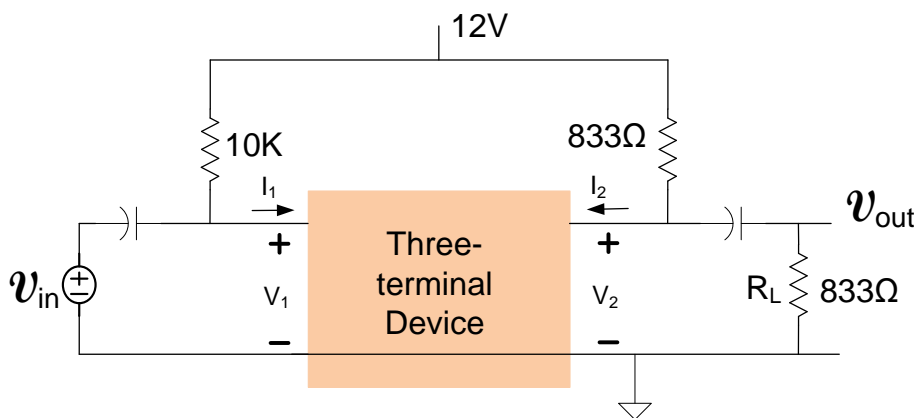
Problem 2 Assume the two capacitors are large and the nonlinear 3-terminal device is characterized by the equations

$$I_1 = 10^{-4} V_1$$

$$I_2 = \left(\frac{V_1 - 4}{10} \right)^3 + 0.002 \cdot V_2$$

- Determine the small-signal model of the nonlinear three-terminal device in terms of the Q-point currents designated as I_{1Q} and I_{2Q}
- Draw a small-signal equivalent network for the whole circuit
- Determine the small-signal voltage gain in terms of the small-signal model parameters of all components in the circuit
- Determine the Q-point currents I_{1Q} and I_{2Q}
- Numerically determine the small-signal voltage gain $A_v = \frac{v_{OUT}}{v_{IN}}$

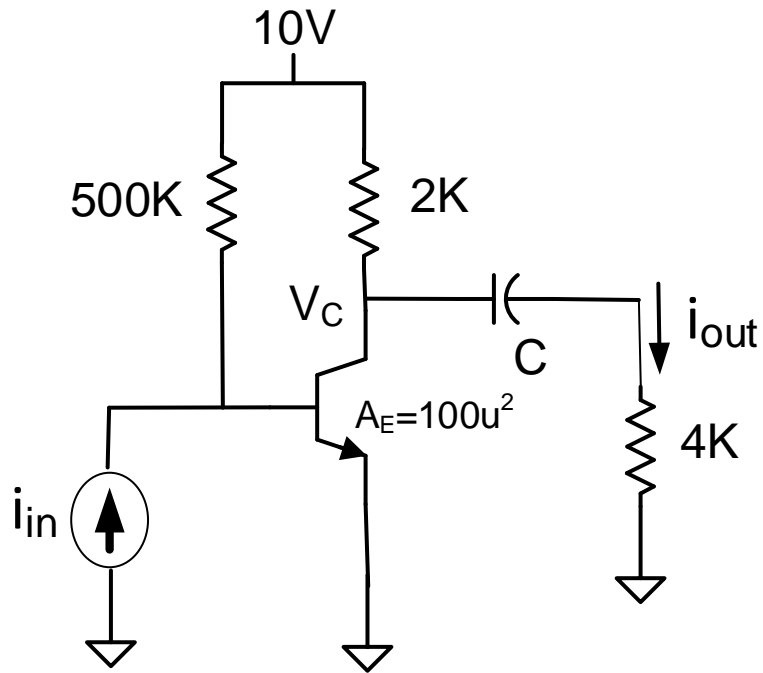
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Continue solution to Problem 2 here if additional space is needed

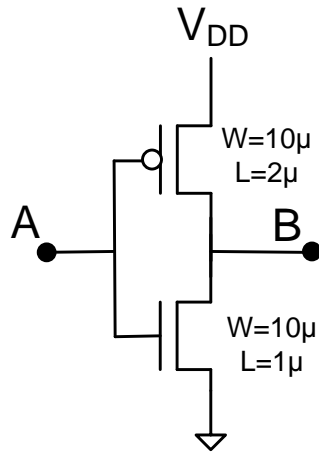
Problem 3 (16 pts) Consider the following circuit where i_{in} is a small-signal input current and the capacitor C is large.

- Determine the quiescent collector voltage.
- Determine the quiescent output current
- Draw the small-signal equivalent circuit
- Derive an expression for the small-signal current gain in terms of the small-signal model parameters
- Numerically determine the small-signal current gain



Problem 4 (16 pts) Design a circuit using only MOS transistors that has an output voltage of 1.2V. You have available any number of MOS transistors and a single 2V dc power supply. Be sure to give the sizes of all transistors. Assume the MOS transistors are from a 1.8V process and have model parameters $\mu_n C_{OX} = 350 \mu A/V^2$ and $V_{Tn} = 0.5V$, and all p-channel transistors have model parameters $\mu_p C_{OX} = 75 \mu A/V^2$ and $V_{Tp} = -0.5V$.

Problem 5 (16 pts) Consider the following circuit designed in a 0.18u CMOS process. Determine the switch-level model for this inverter that includes the input capacitance and the pull-up and pull-down resistors. Assume $V_{DD}=2V$.




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RUN: T68B (MM_NON-EPI)                                VENDOR:
TSMC                                                    FEATURE SIZE: 0.18
TECHNOLOGY: SCN018 microns
Run type: SKD
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INTRODUCTION: This report contains the lot average results obtained by MOSIS from measurements of MOSIS test structures on each wafer of this fabrication lot. SPICE parameters obtained from similar measurements on a selected wafer are also attached.

COMMENTS: DSCN6M018 TSMC

TRANSISTOR PARAMETERS	W/L	N-CHANNEL	P-CHANNEL	UNITS
MINIMUM Vth	0.27/0.18	0.50	-0.51	volts
SHORT Idss	20.0/0.18	547	-250	uA/um
Vth		0.51	-0.51	volts
Vpt		4.8	-5.6	volts
WIDE Ids0	20.0/0.18	14.4	-4.7	pA/um
LARGE Vth	50/50	0.43	-0.42	volts
Vjblk		3.1	-4.3	volts
Ijlk		<50.0	<50.0	pA
K' (Uo*Cox/2)		175.4	-35.6	uA/V^2
Low-field Mobility		416.52	84.54	cm^2/V*s

COMMENTS: Poly bias varies with design technology. To account for mask bias use the appropriate value for the parameters XL and XW in your SPICE model card.

Design Technology	XL (um)	XW um)
SCN6M_DEEP (lambda=0.09)	0.00	-0.01
thick oxide	0.00	-0.01
SCN6M_SUBM (lambda=0.10)	-0.02	0.00
thick oxide	-0.02	0.00

FOX TRANSISTORS	GATE	N+ACTIVE	P+ACTIVE	UNITS
Vth	Poly	>6.6	<-6.6	volts

PROCESS PARAMETERS	N+	P+	POLY	N+BLK	PLY+BLK	M1	M2	UNITS
Sheet Resistance	6.7	7.8	8.0	59.7	313.6	0.08	0.08	ohms/sq
Contact Resistance	10.6	11.0	10.0				4.79	ohms
Gate Oxide Thickness	41							angstrom





































PROCESS PARAMETERS	M3	POLY_HRI	M4	M5	M6	N_W	UNITS
Sheet Resistance	0.08		0.08	0.08	0.03	930	ohms/sq
Contact Resistance	9.24		14.05	18.39	20.69		ohms

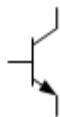
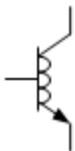
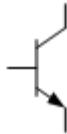


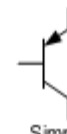
COMMENTS: BLK is silicide block.

CAPACITANCE PARAMETERS	N+	P+	POLY	M1	M2	M3	M4	M5	M6	R_W	D_N_W	M5P	N_W	UNITS	
Area (substrate)	942	1163	106	34	14	9	6	5	3				123	125	aF/um^2
Area (N+active)			8484	55	20	13	11	9	8						aF/um^2
Area (P+active)			8232												aF/um^2
Area (poly)				66	17	10	7	5	4						aF/um^2
Area (metal1)					37	14	9	6	5						aF/um^2
Area (metal2)						35	14	9	6						aF/um^2
Area (metal3)							37	14	9						aF/um^2
Area (metal4)								36	14						aF/um^2
Area (metal5)									34				984		aF/um^2
Area (r well)	920														aF/um^2
Area (d well)										582					aF/um^2
Area (no well)	137														aF/um^2
Fringe (substrate)	212	235		41	35	29	21	14							aF/um
Fringe (poly)				70	39	29	23	20	17						aF/um
Fringe (metal1)					52	34		22	19						aF/um
Fringe (metal2)						48	35	27	22						aF/um
Fringe (metal3)							53	34	27						aF/um
Fringe (metal4)								58	35						aF/um
Fringe (metal5)									55						aF/um
Overlap (N+active)			895												aF/um
Overlap (P+active)			737												aF/um

CIRCUIT PARAMETERS		UNITS
Inverters	K	
Vinv	1.0	0.74 volts
Vinv	1.5	0.78 volts
Vol (100 uA)	2.0	0.08 volts
Voh (100 uA)	2.0	1.63 volts
Vinv	2.0	0.82 volts
Gain	2.0	-23.72
Ring Oscillator Freq.		
D1024_THK (31-stg, 3.3V)	300.36	MHz
DIV1024 (31-stg, 1.8V)	363.77	MHz
Ring Oscillator Power		
D1024_THK (31-stg, 3.3V)	0.07	uW/MHz/gate
DIV1024 (31-stg, 1.8V)	0.02	uW/MHz/gate

Dc and small-signal equivalent elements

	Element	ss equivalent	dc equivalent
dc Voltage Source	V_{DC} 		V_{DC} 
ac Voltage Source	V_{AC} 	V_{AC} 	
dc Current Source	I_{DC} 		I_{DC} 
ac Current Source	I_{AC} 	I_{AC} 	
Resistor	R 	R 	R 
Capacitors	Element	ss equivalent	dc equivalent
	C Large 		
Inductors	C Small 	C 	
	L Large 		
Diodes	L Small 	L 	
			 Simplified
MOS transistors			 Simplified
			 Simplified

	Element	ss equivalent	dc equivalent
Bipolar Transistors			 Simplified
			 Simplified
Dependent Sources	